AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1. (original): A method for producing a light-transmitting electromagnetic wave-shielding film having a conductive metal portion and a light-transmitting portion, which comprises exposing and developing a silver salt-containing layer containing a silver salt and provided on a support to form a metal silver portion and the light-transmitting portion, and further subjecting the metal silver portion to physical development and/or plating to form the conductive metal portion consisting of the metal silver portion carrying conductive metal particles.

2. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 1, wherein the silver salt in the silver salt-containing layer is a silver halide.

3. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 2, wherein the silver halide consists mainly of silver bromide.

4. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 2, wherein the silver halide contains a rhodium compound and/or an iridium compound.

5. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 2, wherein the silver halide contains Pd(II) ions and/or Pd metal.

6. (currently amended): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 1, wherein the silver salt-containing layer contains Ag and a binder and has an Ag/binder volume ratio of 1/4 or higher.

7. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 1, wherein the silver salt in the silver salt-containing layer has a diameter as sphere of 0.1 to 100 nm.

8. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 1, wherein the developer used for the development of the silver salt-containing layer is a lith developer.

9. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 1, wherein an exposed portion after the development contains the metal silver at a content of 50% by weight or more based on the weight of silver contained in the exposed portion before the exposure.

10. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 1, wherein the plating is performed by electroless plating.

11. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 1, wherein the surface of the conductive metal portion is further subjected to a blackening treatment.

12. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 1, wherein the light-transmitting portion does not substantially contain physical development nuclei.

13. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 1, wherein the light-transmitting electromagnetic wave-shielding film has a surface resistance of 2.5 Ω/sq or lower after the physical development and/or plating, and/or the light-transmitting portion has a transmittance of 95% or higher.

14. (withdrawn): A light-transmitting electromagnetic wave-shielding film having a conductive metal portion and a light-transmitting portion, which is obtainable by the production method according to claim 1.

15. (withdrawn): The light-transmitting electromagnetic wave-shielding film according to claim 14, wherein weight of silver contained in the conductive metal portion accounts for 50% by weight or more of the total weight of metal components contained in the conductive metal portion.

16. (withdrawn): The light-transmitting electromagnetic wave-shielding film according to claim 14, wherein the total weight of silver, copper and palladium contained in the conductive metal portion accounts for 80% by weight or more of the total weight of the all metal components.

17. (withdrawn): The light-transmitting electromagnetic wave-shielding film according to claim 14, wherein a layer comprising the conductive metal particles carried by the conductive metal portion has a thickness of 0.1 μm or larger and less than 5 μm and a surface resistance value of 3 Ω/sq or smaller.

18. (withdrawn): The light-transmitting electromagnetic wave-shielding film according to claim 14, wherein the conductive metal portion has a line width of 0.1 μm or larger and smaller than 18 μm.

19. (withdrawn): A plasma display panel having the light-transmitting electromagnetic wave-shielding film according to claim 14.

20. (original): A method for producing a light-transmitting electromagnetic wave-shielding film having a conductive metal portion and a light-transmitting portion, which comprises exposing and developing a silver salt-containing layer containing a silver salt and provided on a support to form a metal silver portion in an exposed portion and the light-transmitting portion in an unexposed portion and further subjecting the metal silver portion to physical development and/or plating to form the conductive metal portion consisting of the metal silver portion carrying conductive metal particles.

21. (previously presented): A method for producing a light-transmitting electromagnetic wave-shielding film according to Claim 1, wherein the support is a plastic film, a plastic plate or a glass plate.